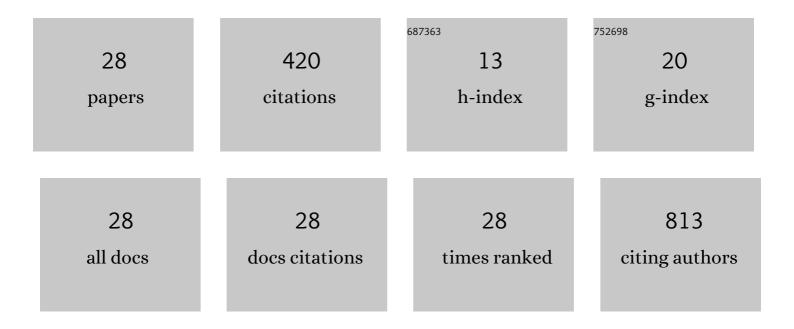
Malgorzata Kot

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/1038688/publications.pdf Version: 2024-02-01



#	Article	IF	CITATIONS
1	Band Bending at Hole Transporting Layerâ€Perovskite Interfaces in nâ€iâ€p and in pâ€iâ€n Architecture. Solar Rrl, 2022, 6, .	5.8	6
2	Toward controlling the Al ₂ O ₃ /ZnO interface properties by <i>in situ</i> ALD preparation. Dalton Transactions, 2022, 51, 9291-9301.	3.3	4
3	Self-Assembled Monolayers from Symmetrical Di-Thiols: Preparation, Characterization and Application for the Assembly of Electrochemically Active Films. Engineering Proceedings, 2021, 6, .	0.4	0
4	Topâ€Down Approach to Study Chemical and Electronic Properties of Perovskite Solar Cells: Sputtered Depth Profiling Versus Tapered Crossâ€5ectional Photoelectron Spectroscopies. Solar Rrl, 2021, 5, 2100298.	5.8	6
5	Low-temperature atomic layer deposition of indium oxide thin films using trimethylindium and oxygen plasma. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, 062406.	2.1	3
6	Atomic Layer-Deposited Aluminum Oxide Hinders lodide Migration and Stabilizes Perovskite Solar Cells. Cell Reports Physical Science, 2020, 1, 100112.	5.6	20
7	In situ Nearâ€Ambient Pressure Xâ€ray Photoelectron Spectroscopy Reveals the Influence of Photon Flux and Water on the Stability of Halide Perovskite. ChemSusChem, 2020, 13, 5722-5730.	6.8	15
8	Thermal stability of CH3NH3PbIxCl3-x versus [HC(NH2)2]0.83Cs0.17PbI2.7Br0.3 perovskite films by X-ray photoelectron spectroscopy. Applied Surface Science, 2020, 513, 145596.	6.1	13
9	Al 2 O 3 â€Atomic Layer Deposited Films on CH 3 NH 3 Pbl 3 : Intrinsic Defects and Passivation Mechanisms. Energy Technology, 2019, 7, 1900975.	3.8	8
10	Point Defect-Mediated Interface Formation and Appearance of a Cooper Minimum for AlO <i>_x</i> Atomic-Layer-Deposited Films on CH ₃ NH ₃ PbI ₃ . Journal of Physical Chemistry C, 2019, 123, 23352-23360.	3.1	7
11	Tailoring optical and electrical properties of thin-film coatings based on mixed Hf and Ti oxides for optoelectronic application. Materials and Design, 2019, 175, 107822.	7.0	25
12	Themed issue on electronic properties and characterisation of perovskites. Journal of Materials Chemistry C, 2019, 7, 5224-5225.	5.5	1
13	Comparison of plasma-enhanced atomic layer deposition AlN films prepared with different plasma sources. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	2.1	8
14	Evidence of Nitrogen Contribution to the Electronic Structure of the CH ₃ NH ₃ PbI ₃ Perovskite. Chemistry - A European Journal, 2018, 24, 3539-3544.	3.3	20
15	Long-term ambient surface oxidation of titanium oxynitride films prepared by plasma-enhanced atomic layer deposition: An XPS study. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, .	2.1	9
16	An (In Situ)2 Approach: ALD and resPES Applied to Al2O3, HfO2, and TiO2 Ultrathin Films. , 2018, , 18-26.		7
17	Interface Potentials, Intrinsic Defects, and Passivation Mechanisms in Al2O3, HfO2, and TiO2 Ultrathin Films. , 2018, , 162-171.		4
18	Roomâ€Temperature Atomicâ€Layerâ€Deposited Al ₂ O ₃ Improves the Efficiency of Perovskite Solar Cells over Time. ChemSusChem, 2018, 11, 3640-3648.	6.8	33

Malgorzata Kot

#	Article	IF	CITATIONS
19	Analysis of surface properties of Ti-Cu-Ox gradient thin films using AFM and XPS investigations. Materials Science-Poland, 2018, 36, 761-768.	1.0	3
20	In-gap states in titanium dioxide and oxynitride atomic layer deposited films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	2.1	14
21	Room temperature atomic layer deposited Al2O3 on CH3NH3PbI3 characterized by synchrotron-based X-ray photoelectron spectroscopy. Nuclear Instruments & Methods in Physics Research B, 2017, 411, 49-52.	1.4	13
22	Selective Deposition of an Ultrathin Pt Layer on a Au-Nanoisland-Modified Si Photocathode for Hydrogen Generation. ACS Omega, 2017, 2, 1360-1366.	3.5	5
23	Analysis of titanium species in titanium oxynitride films prepared by plasma enhanced atomic layer deposition. Surface and Coatings Technology, 2017, 324, 586-593.	4.8	17
24	Localized defect states and charge trapping in atomic layer deposited-Al2O3 films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	2.1	24
25	Roomâ€Temperature Atomic Layer Deposition of Al ₂ O ₃ : Impact on Efficiency, Stability and Surface Properties in Perovskite Solar Cells. ChemSusChem, 2016, 9, 3401-3406.	6.8	76
26	Engineering of Subâ€Nanometer SiO _{<i>x</i>} Thickness in Si Photocathodes for Optimized Open Circuit Potential. ChemSusChem, 2016, 9, 2332-2336.	6.8	16
27	Understanding the growth mechanism of graphene on Ge/Si(001) surfaces. Scientific Reports, 2016, 6, 31639.	3.3	44
28	Analysis of nitrogen species in titanium oxynitride ALD films. Applied Surface Science, 2016, 381, 42-47.	6.1	19